Configuration Details (PECVD)

Plasmalab 100 PECVD

94-100-BW-2FCBL -- System console 2 frame clusterable, PC base unit, 17"TFT, blue plc, PC2000 multi-chamber software & manuals on CD

Console
The PlasmalabSystem100 process module base unit houses all the electronic sub systems, control units, pneumatics, water, gas services and the turbomolecular pumps (if fitted). located in the base unit is the dedicated module control processor.
The module is constructed using proven OPT hardware designs. The extensive OPT process library supports all Plasmalab System 100 configurations. The system is fully interlocked protect the system hardware from any service failure (e.g.. failed water supply for purposes) and to protect the operator from electrical shock during maintenance

PC2000 controller
The control software runs as a WindowsXP application and allows multiple levels of control. Individual users (or class of users) are accessed by password entry.
The system status is displayed on graphic mimic diagrams with all operational parameters status displays accessible through pop-up windows. Recipe programming is provided for all process parameters. Each gas line may be defined, with input of mass flow settings directly sccm.
The software includes full data logging capability of user-selectable run-time process allowing off-line verification and analysis of process
Hardware supplied is a modern specification PC including TFT, keyboard, CD drive, mouse all relevant cards.
Software includes WindowsXP, PC2000 software, and single-user licence.
Operating manuals and parts list are provided on CD.

PLEASE NOTE that as from the 22nd of October 2009 all new systems PCs will run Windows 7. Please contact the sales manager in your area if you have any question or any

94-100-0-415 -- Standard 380V-415V 50Hz System power box

94-100-3-12C-400 -- PECVD process chamber for 400°C electrode with single viewport, 100mm pumping port
The RF-powered top electrode of the PECVD chamber features a large area gas shower-head design for high uniformity. The hinged chamber lid is raised by gas springs for of access for chamber cleaning and maintenance. A 100mm pumping port is

The aluminium process chambers are machined from a single aluminium block to provide vacuum integrity. Each includes a front viewport fitted with an RF shield for viewing the At the rear, a KF40 blanked fitting is provided for OES end-point or other characterisation Included with the process chamber is a MonoVAT isolation valve for connecting the module to the selected wafer insertion device.

94-100-5-400BL -- PECVD 240mm fixed height heated (ambient to 400°C) aluminium grounded lower electrode, with 3 pin lift (without wafer clamping)
240mm diameter resistance heated aluminium electrode for temperatures up to 400°C. height without wafer clamping. Electrically

All electrodes are designed for use with wafers or carrier plates up to 200mm diameter feature an axial lifting mechanism for wafer and carrier plate transfer. Specify wafer size carrier plate details when ordering.

94-100-6-300DBL -- 300W, 13.56MHz RF Generator & Air-vane capacitor Automatch Unit for PECVD

94-100-6-LF5 -- 500W, 350kHz-460kHz Generator & Mixing filter to top electrode for dual frequency PECVD

94-100-7-05 -- 2 Torr capacitance manometer
2 Torr capacitance manometer mounted on the chamber base plate

94-100-8-53 -- 100mm pumping tee with 63mm branch to APC and isolation valve for use with PECVD electrodes (94-100-5-400BL and 94-100-5-700BL)
100mm pumping tee with 63mm branch to separate Automatic Pressure Controller and valve (for use with Roots/rotary pump)

94-100-3-00-17 -- Pumpdown pipe heating kit (100mm pumping tee)
Heating kit applied to the pump-down pipe for optimum vacuum performance and to deposition of loosely adherent material that might generate

94-81-9-51-8 -- 8 line (MAX 8 LINES) externally mounted gas pod
The gas pod is ventilated and fitted with an extraction port for maximum safety. Positions provided for up to 8 mass flow controlled gas lines, with control pneumatics and circuitry for lines included. Fixing points are provided for wall mounting. The gas pod is mounted remote the system console.

94-81-9-11-12 -- (3) Non-toxic gas line excluding mass flow controller
Gas line with stainless steel VCR fittings and orbitally welded joints, including electro-pneumatic isolation valve and one in-line 2µm

94-M/MTR/MFC/ -- (3) MKS 1179A MFC with viton seals for non-corrosive applications
MKS 1179A mass flow controller for use with non-corrosive gases. (CF4, N2, N2O)

94-81-9-21-12 -- (2) Toxic gas line with MFC bypass, excluding mass flow controller
Gas line with stainless steel VCR fittings and orbitally welded joints, including electro-pneumatic isolation valves, one in-line 2µm filter and a manually operated bypass

94-M/MTR/MFC/*M -- (2) MKS 1479A MFC with metal seals for corrosive applications**
MKS 1479A mass flow controller for use with corrosive gases. (5%SiH4/N2, NH3)

94-A300H-415V -- Alcatel A300H 415V 50Hz dry pump with rootes for PECVD (no purge kit required)
Alcatel 300H Dry Pump with Roots for PECVD

94-RIC-A300H -- Integration hardware for AD300H dry pump
Hardware to integrate a dry pump, including purge control and digital

94-100-12-10-1 -- Fixed wavelength endpoint detector for PECVD systems (704nm)
Primarily designed for deposition systems, especially for monitoring atomic fluorine emission 704nm, this product can cover the 185-830 nm (UV-Vis-NIR) range. It includes a wavelength filter that can be specified by the customer's

94-MD91C00001 -- Ø200mm aluminium carrier platen PTN200AL (Recess details must be specified in QCF44)
200mm diameter aluminium carrier plate for 400°C heated

94-CRM -- Clean-room paper system manuals
Set of system operation and maintenance manuals on clean-room compatible paper. OEM unit manuals are not reproduced on clean-room compatible